

Training and usage policy

1. This is a limited & controlled access tool hence no training would be given to anyone outside the group. However outside request can be entertained if approved by the faculty in charge. Any request for measurement should come through a proper channel which first requires a faculty approval.
2. Request needs to be submitted by Thursday afternoon 2 pm, which will be scheduled to be executed on Friday.
3. Maximum number of 2 requests will be served every week on first come first serve basis.
4. The additional requests will be kept in a queue.
5. Requests will not be migrated to other days in case the tool is down on those days.
6. Slots are not transferrable.
7. Room temperature and temperature dependent PL measurement (if approved) will be done, with available facilities.
8. Only thin films or devices made on thin films with III-V semiconductor as a substrate is allowed.
9. Sample history for each sample will be thoroughly checked.
10. Any incomplete or ambiguous declaration will delay the process. Any significant deviation will lead to reviewing this usage policy.

Note: Due to highly sophisticated nature of the tool, lot of precautions are taken to maintain the cleanliness and safety for the tool.

No one is allowed to handle the system or its parts without the presence of an authorized user.

One should hand over the samples to the au well in advance before the measurements.

No other material other than Gallium nitrides and its precursors are allowed.

One should always follow the protocol (Gowning procedure if any) before entering the lab, this is for individual safety as well as the safety of the instrument.